Max-Planck-Institut für Plasmaphysik



# Self-passivating tungsten alloys for first wall applications

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## Outline



- Applications: ITER and DEMO
- Self-passivation mechanism
- Quaternary alloys
- W-Si-Cr bulk materials

## Accidential loss of coolant in reactor



### **Power plant conceptual study**



Temperature profile in PPCS Model A, 10 days after accident with a total loss of all coolant.

[Final Report of the European Fusion Power Plant Conceptual Study, 2004]

- Accidental loss of coolant: peak temperatures of first wall up to 1200 °C due to nuclear afterheat
- Additional air ingress: formation of highly volatile WO<sub>3</sub> (Re, Os)
- Evaporation rate: order of 10 -100 kg/h at >1000°C in a reactor (1000 m<sup>2</sup> surface)
  - $\rightarrow$  large fraction of radioactive WO<sub>3</sub> may leave hot vessel



Development of selfpassivating tungsten alloys

## He-cooled divertor modular design for DEMO (KIT)

### He-cooled multi-jet (HEMJ) concept

### P. Norajitra, KIT



**Goal:**  $\geq$  10 MW/m<sup>2</sup>,

100-1000 load cycles



## He-cooled divertor modular design for DEMO (KIT)



### He-cooled multi-jet (HEMJ) concept



Post-examination after HHF tests at FZJ (90 load cycles at 9 MW/m<sup>2</sup>):

- Formation of thick oxide scale
- Crack propagation



Application for selfpassivating tungsten alloys

P. Norajitra, KIT



Efremov (test range 5-13 MW/m<sup>2</sup>)



### Self passivating tungsten-based alloys:

Surface composition automatically adjusts to the requested property

#### Normal operation (600°C):

Formation of tungsten surface by depletion of alloying element(s) due to preferential sputtering

#### **Accidental conditions:**

(air ingress, up to 1200 °C) Formation of protective barrier layer





### Self passivating tungsten-based alloys:

Surface composition automatically adjusts to the requested property

#### Normal operation (600°C):

TRIDYN numerical simulation of sputter erosion of W-Si-Cr alloy (D ions, 30 eV, fluence 10<sup>18</sup>/cm<sup>2</sup>)



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### **Accidental conditions:**

Cross section of sputter deposited W-Si-Cr film after oxidation at 1000°C for 1h



## Quaternary tungsten based alloys

Addition of reactive elements to W-Si-Cr to improve oxide film formation and adherence

### **Co-deposition by Magnetron sputtering**

- Film thickness ~  $4\mu m$
- SiO<sub>2</sub> and Al<sub>2</sub>O<sub>3</sub> substrates used for oxidation

### **Investigated systems**

- W-Si-Cr-Zr
- W-Si-Cr-Y

(different concentrations)



Schematic view of deposition facility







#### Peak shift due to Lattice Distortion

| d        | 20       | h | k | 1 |
|----------|----------|---|---|---|
| Angström | o        |   |   |   |
| 2,2976   | 39.177   | 1 | 1 | 0 |
| 2,1922   | 41.1438  | 1 | 1 | 0 |
| 1,5567   | 59.3162  | 2 | 0 | 0 |
| 1,3043   | 72.3989  | 2 | 1 | 1 |
| 1,2668   | 74.8987  | 2 | 1 | 1 |
| 0,9823   | 103.2851 | 3 | 1 | 0 |
| 0,8283   | 136.8753 | 3 | 2 | 1 |

- Fifth order polynomial by Gust et al. used to calculate W concentration in assumed binary W-Cr lattice
- *c*(Cr) = 27.5 at-% from peak shift; *c*(Cr) = 29.2 at-% from RBS

Gust, W.; Predel, B.; Roll, U.: Journal of the Less-Common Metals, 69, pp. 331-353, 1980





#### WSi3Cr10Zr5 powder

(annealed at 1000 °C under Ar)

- c(Cr) = 24 at-% after deposition (RBS); c(Cr) = 6.75 at-% after annealing
- Thermodynamic equilibrium: *c*(Cr) = 7 at-% (Gust et al.)
- Cr precipitates from the binary lattice

## **Oxidation experiments**



### Oxidation of W-Si4-Cr8-Y3 at 1000°C for 1 hours



- Heating under inert gas flow
- Start of oxygen at stable temperature

- Parabolic oxidation rates:  $(\Delta m)^2 = k t$ :  $\rightarrow$  Diffusion-governed process
- Two oxidation rates discernible

## XRD analysis: oxidized alloys





 $\rightarrow$  no volatile WO<sub>3</sub> formed!

WSi3Cr10Zr5 (oxidized 1h at 1000 °C)

### **Microstructure of oxidized alloys**



### WSi3Cr10Zr5:



#### SEM of cross section (FIB), 1000°C, 1h



- Dense Cr<sub>2</sub>O<sub>3</sub> barrier scale
- Cr is main diffusing species
- Mixed oxide zone(s)
- Cr depletion zone with voids
- No formation of WO<sub>3</sub>

## **Comparison of oxidation results**



### <u>Arrhenius plot of oxidation rates of tungsten</u> and tungsten alloys



## **Summary: Quaternary alloys**



- Quaternary alloys show better passivation behavior than ternary while containing more W
- Active elements (Y/Zr) do not form oxide layers, but improve oxide scale adhesion
- Surface oxide consists of Cr<sub>2</sub>O<sub>3</sub>
- Oxide phases formed are Cr<sub>2</sub>O<sub>3</sub>, WCrO<sub>4</sub>, WO<sub>2</sub> (2 modifications), ZrSiO<sub>4</sub> (600°C), but no WO<sub>3</sub> → passivation successful
- Two step-oxidation: switch in oxidation mechanism during oxidation
- Different oxidation mechanisms at different temperatures
- Restructuring induced by the precipitation of Cr from the W lattice



### Samples:

8W-Cr-Si2 and 8W-Cr-Si4 nominal composition: W Si10 Cr10

### Investigated properties:

- morphology
- element distribution
- thermal diffusivity
- hardness / Young's modulus
- oxidation behavior

Collaboration with CEIT / San Sebastián

## **Morphology: SEM**





- W phases dominate: gray areas
- pure W (bright) to W alloys
- small oxidic precipitates (no W!)

## 3D analysis: Focused ion beam





#### width of cut: ~75 $\mu$ m

• 3D morphology identical to surface

## **2D element distribution**





### **Cross-section 8W-Cr-Si2**





### **3D element distribution**





## **Thermal diffusivity**





- constant thermal diffusivity
- 50% value of VPS-W



Nanoindenter: micro-hardness, Young's modulus

|   | Micro-hardness<br>[GPa] | Young's modulus<br>[GPa] |
|---|-------------------------|--------------------------|
| alloys:<br>8W-Cr-Si2  | 15.6                    | 320                      |
| 8W-Cr-Si4   | 15.5                    | 321                      |
| comparison:<br>W <sub>f</sub> /W (fiber)<br>W <sub>f</sub> /W (CVD-W) | 9.1—9.8<br>7.5—8.1      | 480—535<br>455—530       |
| (dense bulk W   |                         | 410 <b>)</b>             |

## **Oxidation rates for bulk W Si10 Cr10**



IPP

strong passivation at 800°C, comparable to quaternary alloy layers



Cross section



IPP

Cross section, EDX mapping: Cu





Cross section, EDX mapping: Cr





Cross section, EDX mapping: W



IPP

Cross section, EDX mapping: O





Cross section, EDX mapping: Si (+ W)





### Results of EDX and XRD analysis



### **Bulk alloys: summary**



- W-Cr alloys
- W-Si: hints from XRD
- pure W phase still present in precipitates
- Si-O precipitates
- no visible pores
- oxidation rates promising at 800°C, CrO<sub>x</sub> and Cr<sub>2</sub>WO<sub>6</sub> at 1000 °C

## **Outlook: W alloys**



Further investigations, ideas:

- optimization (Si-free alloys, increase W fraction in quaternary alloys ...)
- production and characterization of bulk alloys (IPP in cooperation with CEIT)
- preferential sputtering with H / D / He ...
- true surface composition at different annealing states
- retention and release of hydrogen isotopes
- comparison of surface layers with bulk alloys (same composition)
- surface chemical reactions as a plasma-facing material ("material mixing")
- → Promising self-passivating material for a reactor application